



In re Application of:
Figura et al.

Serial No.: 09/471,460

Filed: December 22, 1999

For: USE OF A PLASMA SOURCE TO
FORM A LAYER DURING THE
FORMATION OF A SEMICONDUCTOR

Patent

#10/EXT(3)
O'Had
6/6/01

§ Group Art Unit: 2825
§
§ Examiner: Calvin Lee
§
§ Atty. Docket: 94-0280.03
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Certificate of Mailing (37 C.F.R. § 1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to Commissioner for Patents, Washington, D.C. 20231, on the date below:

5-21-01
Date

Irish Thomas Davis
Signature

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136(a)

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Applicant hereby petitions to extend the period for response to the Office Action mailed November 21, 2000 for three (3) months, from 2/21/01 to 5/21/01.

Accordingly, the requisite fee is \$ 890. The Commissioner is requested to charge this fee, and any additional fee which may be required to Micron Technology, Inc. Deposit Account 13-3092, Order No. 94-0280.03. A duplicate copy of this petition is enclosed.

Respectfully submitted,

Date: 5/21/01

Charles Brantley

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